

MICROELECTRONIC CLEANING COMPOSITION CONTAINING HALOGEN OXYGEN ACIDS, SALTS AND DERIVATIVES THEREOF

Abstract

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Microelectronic cleaning compositions for cleaning microelectronic substrates,
and particularly cleaning compositions useful with and having improved
compatibility with microelectronic substrates characterized by silicon dioxide,
sensitive low-k or high-k dielectrics and copper, tungsten, tantalum, nickel, gold,
10 cobalt, palladium, platinum, chromium, ruthenium, rhodium, iridium, hafnium,
titanium, molybdenum, tin and other metallization, as well as substrates of Al or
Al(Cu) metallizations and advanced interconnect technologies, are provided by
microelectronic cleaning compositions comprising halogen acids, salts and
derivatives thereof.